Notice of Allowability	Application No.	Applicant(s)
	10/787,487	CLEVENGER ET AL.
	Examiner	Art Unit
	Toniae M. Thomas	2822
The MAILING DATE of this communication apperature All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this app or other appropriate communication IGHTS. This application is subject to	olication. If not included will be mailed in due course. THIS
1. $\boxtimes$ This communication is responsive to <u>the amendment filed</u>	on 29 September 2005.	
2. X The allowed claim(s) is/are 11-15 and 17-23.		
<ul> <li>3: Acknowledgment is made of a claim for foreign priority una)</li> <li>All b) Some* c) None of the:</li> <li>1. Certified copies of the priority documents have</li> <li>2. Certified copies of the priority documents have</li> <li>3. Copies of the certified copies of the priority documents have</li> <li>International Bureau (PCT Rule 17.2(a)).</li> <li>* Certified copies not received:</li> </ul>	been received. been received in Application No	
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		complying with the requirements
4. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give		
5. CORRECTED DRAWINGS (as "replacement sheets") must be submitted.		
(a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review ( PTO-948) attached		
1)  hereto or 2)  to Paper No./Mail Date		
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date	s Amendment / Comment or in the O	ffice action of
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in t	.84(c)) should be written on the drawin he header according to 37 CFR 1.121(c	ngs in the front (not the back) of d).
6. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT		
Attachment(s)	5 🗖 11 (1) (1) (1)	
<ol> <li>Notice of References Cited (PTO-892)</li> <li>Notice of Draftperson's Patent Drawing Review (PTO-948)</li> </ol>		atent Application (PTO-152)
_	6. ⊠ Interview Summary Paper No./Mail Dat	e <u>12122005</u> .
<ol> <li>Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date</li> </ol>	8), 7. 🛛 Examiner's Amendr	nent/Comment
4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. X Examiner's Stateme	nt of Reasons for Allowance
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		Mary Wilczewski Drimary Examiner

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## **EXAMINER'S AMENDMENT**

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Mohammed Rahman on 12 December 2005.

## **Amendment**

2. The application has been amended as follows:

## In Claims

In Claim 12, line 8,

--removing said sacrificial gate structure-- has
been inserted after "a gate region;";

In Claim 14, line 7,

--removing a sacrificial gate structure from said

gate region-- has been inserted after "gate region;".

## Reasons for Allowance

3. The following is an examiner's statement of reasons for allowance: the prior art of record does not anticipate or render obvious a method of forming a metal-insulator-metal capacitor and an associated semiconductor transistor having a metal gate. Specifically, there is no motivation or suggestion in Moriwaki to substitute a metal layer for the polysilicon layer 303. Moriwaki teaches to form the sacrificial gate structure 303 from a polysilicon layer, and

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then subsequently remove the sacrificial gate structure and replace it with a metal layer. Since the bottom electrode of the capacitor 303C, gate electrode 303A, and sacrificial gate structure 303B are all formed simultaneously from the same polysilicon layer, substitution of the polysilicon layer with a metal layer would render the removal step and subsequent metal deposition step unnecessary. Hence, it is deemed that Moriwaki cannot be modified to use a metal layer in place of the polysilicon layer 30.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Toniae M. Thomas whose telephone number is (571) 272-1846. The examiner can normally be reached on Monday through Friday from 8:30 a.m. to 5:30 p.m.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Zandra Smith can be reached on (571) 272-2429. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

TMT 12 December 2005 Mary Wilczewski Primary Examiner